

**SUBSTRATE BRUSH SCRUBBING AND
PROXIMITY CLEANING-DRYING SEQUENCE
USING COMPATIBLE CHEMISTRIES, AND METHOD,
APPARATUS, AND SYSTEM FOR
IMPLEMENTING THE SAME**

ABSTRACT OF THE DISCLOSURE

A method for cleaning and drying a front and a back surface of a substrate is provided. The method includes brush scrubbing the back surface of the substrate using a brush scrubbing fluid chemistry. The method further includes applying a front meniscus onto the front surface of the substrate upon completing the brush scrubbing of the back surface. The front meniscus includes a front cleaning chemistry that is chemically compatible with the brush scrubbing fluid chemistry.